

Your Ref.: P16710TW
Our case No.: 845819
Appln. No.: 93130021
Present Stage: Primary Examination
Type of Notice: Office Action
Cited Reference: Y(6)

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[TRANSLATION OF THE NOTICE]

Syllabus:

Upon examination, this application No.93130021 is found to be with obscurities as stated in Explanation 1 below. The applicant may submit a supplementary exposition in duplicate or make an amendment within sixty days post the service of this notice as the reply to this notice if so desired. However, if the above-mentioned time limit is not observed duly, a decision will be rendered based on the contents presently available*. (*TIPLO note: indicating that the application shall likely be rejected if the official instruction(s) are not followed within the time limit.)

Explanation:

1. After examination, the present application is held as follows.
 - 1.1 The present application was examined based on the material that was submitted when the present application was filed. The present application contains 40 claims wherein claims 1, 11, 16, 20, 25, 30, 34 and 37 are independent claims and the rest of the claims are dependent claims.
 - 1.2 Claims 1, 3 to 5, 8, 11 to 17, 20, 25, 30, 32, 34 and 36 of the present application do not meet the requirements of paragraph 1 in Article 22 of Taiwan Patent Law. Claims 2, 9, 10, 18, 19, 21 to 24, 26 to 29, 33 and 35 of the present application do not meet the requirements of paragraph 4 in Article 22 of Taiwan Patent Law.
 - 1.3 Claims 3, 18 and 25 to 28 of Taiwan patent publication No. 499706 and the abstract of Japan patent publication No. 10106930 disclose treating an unexposed photoresist with an electric field. Thus, claim 1 of the present application does not have any novelty.
Claims 3 to 5 of the present application are disclosed in Japan patent publication No. 10106930 and thus do not have any novelty.

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Claim 8 of the present application is disclosed in US Patent No. 6103145 and thus does not have any novelty.

- 1.4 Claims 11 to 13 of the present application are disclosed in Japan patent publication No. 63244622. Claims 13 to 15 of the present application are disclosed in US Patent No. 6103145. Thus, claims 11 to 15 of the present application do not have any novelty.
- 1.5 Claims 16 and 17 of the present application are disclosed in US Patent No. 5648000 and thus do not have any novelty.
- 1.6 Claim 20 of the present application is disclosed in Japan patent publication No. 63244622. Claim 25 of the present application is disclosed in Japan patent publication No. 10106930. Claims 30 and 32 of the present application are disclosed in US patent publication No. 20020046703. Thus, claims 20, 25, 30 and 32 of the present application do not have any novelty.
- 1.7 Japan patent publication No. 10106930 discloses a structure wherein a photosensitive functional group of the photoresist layer on a wafer is fixed. Thus, claims 34 and 36 of the present application do not have any novelty.
- 1.8 The features of the method claimed by claims 2, 9, 10, 18, 19, 21 to 24, 26 to 29 and 33 of the present application are not recited in the cited references above. However, the difference between these claims and the cited references is a basic knowledge in the same field. The difference can be easily accomplished by a person having ordinary skill in the same field by combining Japan patent publication No. 10106930 or Japan patent publication No. 63244622 with suitable techniques due to the actual needs. Thus, claims 2, 9, 10, 18, 19, 21 to 24, 26 to 29 and 33 of the present application do not have any inventive step.
- 1.9 Claim 35 of the present application is not disclosed in Japan patent publication No. 10106930. However, the feature of claim 35 is an ordinary skill and can be easily accomplished by a person having ordinary skill in the same field due to the actual needs. Thus, claim 35 does not have any inventive step.

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2. If the specification and drawings are to be amended or supplemented, in accordance with the provision of Article 28 of the Enforcement Rules of the Patent Law, a request form has to be filed in duplicate, along with the supplementary amended pages of the specification or drawings in duplicate (with the supplement or amended portions underlined) and a clean-copy of the supplemented/amended pages of the specification or drawings in triplicate; and if this supplement or amendment results in discontinuity in the number of pages of the original specification or drawings, a complete set of the specification or drawings after supplement/amendment has to be submitted to this Office in triplicate.
3. If an interview or demonstration is desired by the applicant and an application for an interview stated in the reply to this notice is made by the applicant, such interview or demonstration may be arranged by this Office when it is considered needed, and a government fee of NT\$ 1,000 shall be paid.
4. Attached is a copy of the search report of the present application.

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Taiwan IPO Search Report

Taiwan Invention Patent Application No. 93130021

1. Filing date: October 4, 2004		
2. Priority date: October 6, 2003		
3. International Patent Classification (IPC): G03F7/20 (2006.01)		
4. Technical fields searched (IPC): G03F7/20 (2006.01)		
5. Database (keywords) searched: TIPO Domestic and Foreign Patent Database (photoresist, electric field), EPO (resist, electric field), USPTO (resist, electric field), JPO (resist, electric field)		
Category	Citation of Document with Indication of Relevant Passage	Relevant to Claim No.
X	1. TW 499706 2002/08/21 Claims 3, 18 and 25 to 28	1
X	2. JP 10106930 1998/04/24 All	1, 3 to 5, 25, 34, 36
Y		2, 9, 10, 18, 19, 26 to 29, 32, 33, 35
X	3. JP 63244622 1988/10/12 Abstract	11 to 13, 20 21 to 24
Y		
X	4. US 6103145 2000/08/15 Abstract	1, 8, 13 to 15
X	5. US 5648000 1997/07/15 Abstract	16, 17
X	6. US 20020046703 2002/04/25 Abstract	30, 32

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Category of the cited documents:

X: document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone.

Y: document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents.

A: document defining the general state of the art.

D: document cited in the application.

E: earlier patent document, but published on, or after the filing date.

O: document referring to public use, sale or exhibition.

P: document published prior to the filing date but later than the priority date.

L: document cited for other reasons.

Date of completion of the search: August 27, 2007

正本

檔 號
發文人員

經濟部智慧財產局 審查意見通知函

104 雙掛號
臺北市中山區南京東路2段125號7樓

機關地址：台北市辛亥路2段185
號3樓
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受文者：英特爾股份有限公司（代理人：林志剛先生）

發文日期：中華民國96年8月29日
發文文號：(96)智專二(六)01088字第
09620482550號 
速別：
密等及解密條件或保密期限：
附件：如文

主旨：第093130021號專利申請案經審查後認有如說明一所述情事，
台端（貴公司）請於文到次日起60日內提出申復說明（一式2份）或修正至局。逾期未復者，本局將依現有資料續行審查，請查照。

說明：

一、本案經審查認為：

(一) 本案依申請時所送資料內容審查，申請專利範圍計40項，其中第1、11、16、20、25、30、34、37項為獨立項，其餘為附屬項。

(二) 申請專利範圍第1、3—5、8、11—17、20、25、30、32、34、36項，不符專利法22條第1項規定；申請專利範圍第2、9、10、18、19、21—24、26—29、33、35項，不符專利法22條第4項規定。

(三) 申請專利範圍第1項，已公開資料如TW 499706 (claim 3、18、25—28) 或JP 10106930 (abstract) 揭示以電場處理未曝光之光阻，不具新穎性。第3—

5項之請求亦見於JP 10106930中，不具新穎性。第8項公開於US6103145 (abstract)，不具新穎性。

(四)申請專利範圍第11—15項，已揭示於JP63244622(第11—13項)或US6103145(第13—15項)，不具新穎性。

(五)申請專利範圍第16、17項，已揭示於US5648000，不具新穎性。

(六)申請專利範圍第20、25、30、32項，已揭示於公開資料JP63244622(第20項)、JP10106930(第25項)、US2002046703(第30、32項)，不具新穎性。

(七)申請專利範圍第34、36項之結構，JP10106930揭示晶圓上的光阻層的感光官能基經定位之結構，第34、36項，不具新穎性。

(八)申請專利範圍第2、9、10、18、19、21—24、26—29、33項之方法，所述之特點雖未明述於上掲引證案中，惟不同處係所屬技術領域中的基本知識範圍，所屬技術領域中具通常知識者自能因應實際需要而選用適合之技術知識結合JP10106930或JP63244622[而輕易完成，不具進步性。

(九)申請專利範圍第35項，雖未揭示於JP10106930中，惟所述特點係一般之知識，所屬技術領域中具通常知識者自能因應實際需要而輕易完成，不具進步性。

二、如有補充、修正說明書或圖式者，依專利法施行細則第28條之規定，應備具補充、修正申請書一式2份，並檢送補充、修正部分劃線之說明書或圖式修正頁一式2份及補充、修正後無劃線之說明書或圖式替換頁一式3份；如補充、修正後致原說明書或圖式頁數不連續者，應檢附補充、修正後之全份說明書或圖式一

式3份至局。

三、若希望來局當面示範或說明，請於申復說明書內註明
「申請面詢」並繳交規費新台幣1千元正，本局認為有
必要時，將另行通知面詢地點及時間。

四、檢送本案檢索報告1份。

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經濟部智慧財產局

附件

第 093130021 號專利申請案檢索報告

1. 申請日：93 年 10 月 4 日		
2. 優先權日：2003 年 10 月 6 日		
3. 本案國際專利分類號(IPC)：G03F7/20 (2006.01)		
4. 檢索國際專利分類號(IPC)範圍： G03F7/20 (2006.01)		
5. 檢索使用資料庫名稱(關鍵詞)： TIPO 國內外專利資料庫(光阻 電場), EPO(resist "electric field"), USPTO(resist "electric field"), JPO(resist "electric field")		
關聯性代碼	引用文獻資料與相關段落處	相關聯請求項
X	1. TW 499706 2002/08/21 申請專利範圍第3、18、25~28項	1
X	2. JP 10106930 1998/04/24 全文	1, 3-5, 25, 34, 36
Y		2, 9, 10, 18, 1, 26-29, 32, 3, 35
X	3. JP 63244622 1988/10/12 摘要	11~13, 20
Y		21~24
X	4. US 6103145 2000/08/15 摘要	1, 8, 13~15
X	5. US 5648000 1997/07/15 摘要	16, 17
X	6. US 2002046703 2002/04/25 摘要	30, 32
關聯性代碼說明： X：單獨引用即足以否定發明新穎性或進步性之特別相關的文獻。 Y：結合一或多篇其他文獻後足以否定發明進步性之特別相關的文獻。 A：一般技術水準之參考文獻。 D：說明書已記載之文獻。 E：申請在前、公開／公告在後之專利文獻。 O：公開使用、販賣或展覽陳列之文件。 P：申請日與優先權日間公開之文獻。 L：其他理由引用之文獻。		

完成日：96 年 8 月 27 日